

	Hits	Search Text	DBs
13	78	((resist or photoresist) same (surfactant or (non\$3ionic near3 surfactant) or (amphoteric near3 surfactant) or (cationic near3 surfactant))) and (resin\$3 same (polyvinyl near3 (alcohol or acetal or acetate)) same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and ((resist or photoresist) near9 (thick\$6 or imprpov\$4 or adher\$4) near9 (material or composition or layer or coat\$4 or film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	27	((resist or photoresist) same (surfactant or (non\$3ionic near3 surfactant) or (amphoteric near3 surfactant) or (cationic near3 surfactant))) and (resin\$3 same (polyvinyl near3 (alcohol or acetal or acetate)) same (cyclic or water\$3soluble or alkali\$3soluble or aromatic or alicyclic or heterocyclic or polyphenol or naphthalene\$3polyhydroxy or benzophenone or flavonoid or polycycloalkane or (aromatic near3 carboxylic) or cycloalkane) same ((alkali\$3 or water) near2 solub\$5)) and ((resist or photoresist) near9 (thick\$6 or imprpov\$4 or adher\$4) near9 (material or composition or layer or coat\$4 or film) near9 pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB